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- (71) 申请人: 盛美半导体设备(上海)股份有限公司(**ACM RESEARCH (SHANGHAI), INC.**) [CN/CN];
中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。
- (72) 发明人: 盛俊威(**SHENG, Junwei**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690

号第4幢, Shanghai 201203 (CN)。贾照伟(**JIA, ZhaoWei**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。秦岭(**QIN, Ling**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。杨宏超(**YANG, Hongchao**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。王坚(**WANG, Jian**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。王晖(**WANG, Hui**); 中国上海市浦东新区中国(上海)自由贸易试验区蔡伦路1690号第4幢, Shanghai 201203 (CN)。

(74) 代理人: 上海专利商标事务所有限公司(**SHANGHAI PATENT & TRADEMARK LAW OFFICE, LLC**); 中国上海市徐汇区桂平路435号, Shanghai 200233 (CN)。

(54) **Title:** SUBSTRATE CARRYING STRUCTURE

(54) 发明名称: 基板承载结构

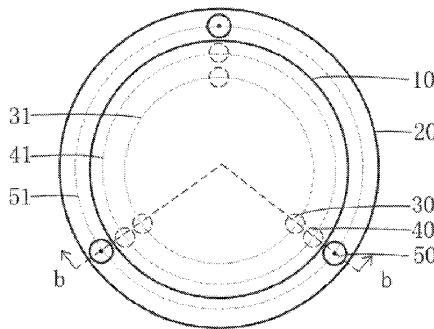


图 4

(57) **Abstract:** Disclosed in the present invention is a substrate carrying structure. The substrate carrying structure comprises: a base, wherein the surface of the base is provided with a carrying area used for carrying a substrate; a plurality of supporting pieces, arranged on a first circumference of the carrying area, wherein a supporting surface is provided at the top end of each supporting piece and used for supporting the substrate; a plurality of guide pieces, arranged on a second circumference on the periphery of the carrying area, wherein the first circumference and the second circumference are concentric circles taking the center of the carrying area as the center of a circle, and the guide pieces are higher than the supporting pieces and used for horizontally limiting the substrate; and a plurality of slide guiding pieces, arranged in the carrying area, wherein the whole or part of each slide guiding piece is located between the first circumference and the second circumference, the slide guiding pieces are not higher than the supporting pieces, a slide guiding surface is provided at the top end of each slide guiding piece, and the friction coefficient of each slide guiding surface is smaller than the friction coefficient of each supporting surface. In the present invention, the effect of improving the substrate guiding capacity of a substrate supporting structure is achieved by means of the structure.

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本国际公布:
— 包括国际检索报告(条约第21条(3))。

(57) 摘要: 本发明公开了一种基板承载结构, 该基板承载结构包括: 底座, 底座表面具有承载区域, 用于承载基板; 若干支撑件, 设置于承载区域的第一圆周, 支撑件顶端具有支撑面, 用于支撑基板; 若干导向件, 设置于承载区域外围的第二圆周, 且第一圆周和第二圆周为以承载区域中心为圆心的同心圆, 且导向件高于支撑件, 用于水平限位基板; 若干导滑件, 设置于承载区域, 导滑件的全部或局部位于第一圆周和第二圆周之间, 且导滑件不高于支撑件, 导滑件顶端具有导滑面, 导滑面的摩擦系数小于支撑面的摩擦系数。本发明通过上述结构实现了提升基板支撑结构对基板导向能力的效果。